Supplemental figure

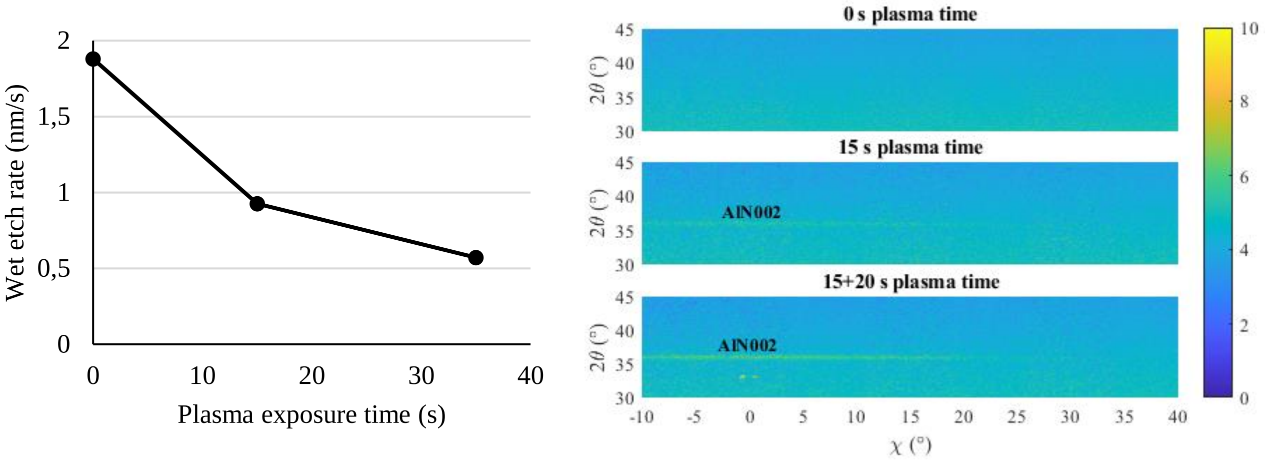

Figure 1: Etch rate in diluted AZ 351B as a function of applied plasma time per cycle on the left and AlN002 XRD reflection on the right. Longer plasma exposure enhances the crystal quality and lowers the etch rate.